# **Guojin Chen**

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## **Current Position**

Visiting Student, The University of Texas at Austin 2023.08 – Present

Supervisor: Prof. David Z. Pan

**Ph.D. Candidate**, The Chinese University of Hong Kong 2021.08 – Present

Supervisor : Prof. Bei Yu

## **Education**

Ph.D. in Computer Science, The Chinese University of Hong Kong	2021 – Present
M.S. in Computer Science, The Chinese University of Hong Kong	2019 - 2020
B.S. in Computer Science, Huazhong University of Science and Technology	2015 - 2019

#### **Research Interests**

- Design for manufacturing (DFM) / Electronic design automation (EDA)
- Computational lithography / Resolution enhancement technologies
- Deep Learning for VLSI / Physics-informed deep learning

## Publications [Google Scholar; 110+ citations, h-index: 5+]

Representative publications that I am a primary author on are highlighted.

## Conference papers.....

- [C15] Efficient Bilevel Source Mask Optimization

  Guojin Chen, Hongquan He, Peng Xu, Hao Geng, and Bei Yu

  (DAC 2024) ACM/IEEE Design Automation Conference
- [C14] Fracturing-aware Curvilinear ILT via Circular E-beam Mask Writer Xinyun Zhang, Su Zheng, Guojin Chen, Binwu Zhu, Hong Xu, and Bei Yu (DAC 2024) ACM/IEEE Design Automation Conference
- [C13] Performance-driven Analog Routing via Heterogeneous 3DGNN and Potential Relaxation Peng Xu, Guojin Chen, Keren Zhu, Tinghuan Chen, Tsung-Yi Ho, and Bei Yu (DAC 2024) ACM/IEEE Design Automation Conference
- [C12] Open-Source Differentiable Lithography Imaging Framework Guojin Chen, Hao Geng, Bei Yu, and David Z. Pan (SPIE 2024) SPIE Advanced Lithography + Patterning
- [C11] AlphaSyn: Logic Synthesis Optimization with Efficient Monte Carlo Tree Search Zehua Pei, Fangzhou Liu, Zhuolun He, Guojin Chen, Haisheng Zheng, Keren Zhu, and Bei Yu (ICCAD 2023) Proceedings of the 42th International Conference on Computer-Aided Design
- [C10] Physics-Informed Optical Kernel Regression Using Complex-valued Neural Fields

  Guojin Chen, Zehua Pei, Haoyu Yang, Yuzhe Ma, Bei Yu, and Martin Wong

  (DAC 2023) ACM/IEEE Design Automation Conference (Best score in DFM track.)
- [C9] DiffPattern: Layout Pattern Generation via Discrete Diffusion Zixiao Wang, Yunheng Shen, Wenqian Zhao, Yang Bai, Guojin Chen, Farzan Farnia, and Bei Yu (DAC 2023) ACM/IEEE Design Automation Conference
- [C8] GPU-accelerated Matrix Cover Algorithm for Multiple Patterning Layout Decomposition Guojin Chen, Haoyu Yang, and Bei Yu (SPIE 2023) DTCO and Computational Patterning II

- [C7] Efficient Point Cloud Analysis Using Hilbert Curve.
  Wanli Chen, Xinge Zhu, Guojin Chen, and Bei Yu
  (ECCV 2022) European Conference on Computer Vision
- [C6] AdaOPC: A Self-Adaptive Mask Optimization Framework For Real Design Patterns Wenqian Zhao, Xufeng Yao, Ziyang Yu, **Guojin Chen**, Yuzhe Ma, Bei Yu, and Martin Wong (ICCAD 2022) Proceedings of the 41th International Conference on Computer-Aided Design
- [C5] LayouTransformer: Generating Layout Patterns with Transformer via Sequential Pattern Modeling Liangjian Wen, Yi Zhu, Lei Ye, **Guojin Chen**, Bei Yu, Jianzhuang Liu, and Chunjing Xu (ICCAD 2022) Proceedings of the 41th International Conference on Computer-Aided Design
- [C4] DevelSet: Deep Neural Level Set for Instant Mask optimization

  Guojin Chen, Ziyang Yu, Hongduo Liu, Yuzhe Ma, and Bei Yu

  (ICCAD 2021) Proceedings of the 40th International Conference on Computer-Aided Design
- [C3] Learning Point Clouds in EDA.
  Wei Li, Guojin Chen, Haoyu Yang, Ran Chen, and Bei Yu
  (ISPD 2021) ACM International Symposium on Physical Design
- [C2] DAMO: Deep Agile Mask Optimization for Full Chip Scale

  Guojin Chen, Wanli Chen, Yuzhe Ma, Haoyu Yang, and Bei Yu

  (ICCAD 2020) Proceedings of the 39th International Conference on Computer-Aided Design
- [C1] A GPU-enabled Level Set Method for Mask Optimization
  Ziyang Yu, Guojin Chen, Yuzhe Ma, and Bei Yu
  (DATE 2020) IEEE/ACM Proceedings Design, Automation and Test in Europe

#### Journal papers

- [J5] Ultra-Fast Source Mask Optimization via Conditional Discrete Diffusion

  Guojin Chen, Zixiao Wang, Bei Yu, David Z. Pan, and Martin D.F. Wong

  (TCAD 2024) IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems
- [J4] L2O-ILT: Learning to Optimize Inverse Lithography Techniques
  Binwu Zhu, Su Zheng, Ziyang Yu, **Guojin Chen**, Yuzhe Ma, Fan Yang, Bei Yu, and Martin Wong
  (**TCAD 2023**) *IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems*
- [J3] A GPU-Enabled Level-Set Method for Mask Optimization
  Ziyang Yu, Guojin Chen, Yuzhe Ma, and Bei Yu
  (TCAD 2023) IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems
- [J2] DevelSet: Deep Neural Level Set for Instant Mask optimization

  Guojin Chen, Ziyang Yu, Hongduo Liu, Yuzhe Ma, and Bei Yu

  (TCAD 2023) IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems
- [J1] DAMO: Deep Agile Mask Optimization for Full-Chip Scale **Guojin Chen**, Wanli Chen, Qi Sun, Yuzhe Ma, Haoyu Yang, and Bei Yu

  (**TCAD 2022**) *IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems*

# **Open Source Repositories**

1. OpenOPC/OpenILT — ★68 — Open-source inverse lithography technology (ILT) framework	2023
2. ai4eda/awesome-Al4EDA — $\star$ 80 — A curated paper list of existing AI for EDA studies.	2023

# **Experiences**

Research Assistant, The Chinese University of Hong Kong	2020 - 2021
Research Intern, Tencent	2018 - 2019

## **Awards**

Ph.D. Studentship

By Chinese University of Hong Kong, 2021-2025

Outstanding Graduate

2021 – 2025

2019

# **Ongoing Projects**

Differentiable Computational Lithography. Revamping lithography with a GPU-accelerated, differentiable workflow based on Abbe imaging, using automatic differentiation to target diverse resolution enhancement objectives.

# **Professional Activities**

Paper Review / External Review.	
Design Automation Conference (DAC)	2021-2023
AAAI Conference on Artificial Intelligence (AAAI)	2022-2023
IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems (TCAD)	2022-2023